



ABSTRACT OF THE DISCLOSURE (FIG. 8)

"RESIST PROCESSING METHOD AND RESIST PROCESSING SYSTEM"

A resist processing method for introducing a pressurized gas into a vessel 1 storing a processing solution, sending the processing solution from the vessel 1 to a nozzle 12 by way of a supply line by means of the pressurized gas, and supplying the processing solution from the nozzle 12 to a substrate W, the method comprising the steps of (a) attaching a deaeration mechanism to the supply line, the deaeration mechanism having a gas-liquid separation membrane 64a and a vacuum evacuation line 51, (b) introducing the pressurized gas into the vessel to send out a processing solution from the vessel into one side portion of the gas-liquid separation membrane through the supply line, (c) evacuating the other side portion of the gas-liquid separation membrane through the vacuum evacuation line 51 to set the pressure of the other side portion of the gas-liquid separation membrane within a saturated vapor pressure of the processing solution, permitting a liquid component dissolved in the processing solution to migrate from the one side portion to the other side portion, thereby removing a gaseous component from the processing solution before the solution is supplied to a substrate (deaeration step), (d) discharging the processing solution present in the supply line between the

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deaeration mechanism and the nozzle, and introducing
the processing solution deaerated in the deaeration
step into the supply line between the deaeration
mechanism and the nozzle, (e) supplying the deaerated
5 processing solution to the substrate by expelling the
deaerated processing solution from the nozzle 12, and
(f) rotating the nozzle relative to the substrate to
form a liquid film of the deaerated processing solution
between the nozzle 12 and the substrate.

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